October 21 (Wed.), 2026

[Oral 09] Sustainable CMP / Manufacturing Readiness

16:50-17:55

International Conference Hall (B1F)

● Session Chair: Knut Gottfried (Fraunhofer ENAS, Germany)

16:50-17:15 [Oral 09-1]	**[Invited]** CMP Challenges and Opportunities for 3D Silicon Photonics Aurore Durel (STMicroelectronics, France) and Catherine Euvrard (CEA- LETI, France)
17:15-17:35 [Oral 09-2]	CMP as a Key Enabling Process Step for SiGe BiCMOS, Silicon Photonics, and Quantum Technologies Marco Lisker, Awwal Adeniyi Adesunkanmi, and Andreas Krüger (IHP GmbH - Leibniz Inst. for High Performance Microelectronics, Germany)
17:35-17:55 [Oral 09-3]	Recyclability of Cu/Ta Barrier Slurry via Ultrafiltration Max Constantin Klotzsche, Conrad Guhl (Fraunhofer IPMS, Germany), and Frank Babick (Technische Univ. Dresden, Germany)